



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant	:	Fukuda et al.)	Group Art Unit 1763
)	
Appl. No.	:	09/511,934)	
)	
Filed	:	February 24, 2000)	
)	
For	:	THIN-FILM FORMING) APPARATUS HAVING AN) AUTOMATIC CLEANING) FUNCTION FOR CLEANING) THE INSIDE))	
)	
Examiner	:	R. Kackar)	

RECEIVED
MAR 31 2003
TC 1700

AMENDMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

Dear Sir:

In response to the Office Action mailed November 20, 2002 (Paper number 13), please amend the above-identified application as follows:

IN THE CLAIMS:

Please cancel Claim 8.

Please amend Claim 1 as follows:

1. (Fifth amended) A thin film forming apparatus comprising:

a reaction chamber for forming at a film formation temperature of 500°C or higher a thin film on a workpiece placed on a susceptor and below a showerhead provided in the reaction chamber, said susceptor being made of aluminum nitride and provided with a heater for heating the workpiece, said reaction chamber being provided with a conveyer for loading and unloading the workpiece into and from the reaction chamber; and

a cleaning device for cleaning unwanted deposits adhering to the inside of the reaction chamber at predetermined intervals, said cleaning device comprising: